# Apogee™ Bake Plate

## With DataStream™ Technology

Cee® Apogee™ bake plate features a revolutionary intuitive interface, a space-saving design, and track-quality thermal accuracy and uniformity.

*Serving the Semiconductor Industry Since 1987*

## BENEFITS

- New compact design for minimized footprint
- Full-color, 7-inch touch screen display
- Durable benchtop design that can be converted to a flange-/deck-mountable configuration
- Enhanced logging and optional programmable height control
- Hot plate cover that is cool to the touch, adding extra safety benefits
- Programmable exhaust
- Lift pins are now a standard inclusion
- DataStream™ technology as the standard interface

## PROGRAMMABILITY

- Touch screen interface and display
- Virtually unlimited recipe storage
- Virtually unlimited steps per program
- 0.1-s resolution for step times with a range of 0 to 9,999.9 s/step
- Three automated bake methods: contact, vacuum, proximity
- Bake plate auto-sizing for 3-inch, 100-, 125-, 150-, and 200-mm substrates
- Temperature data recording
- Electronic lift pins programmable in 0.1-mm increments with an overall range of 0 to 13 mm
- Security – password protection available at no charge

## PRECISION

- Substrate sizes: < 1 cm to 200 mm round; 8 inches × 8 inches square
- Temperature resolution: 0.1°C
- Temperature range: ambient to 300°C (400°C optional)
- Temperature uniformity: 0.3% across working surface



## DIMENSIONS

- 13.25 inches (33.65 cm) W × 19 inches (48.26 cm) D × 12 inches (30.48 cm) H
- Machine weight: 65 lb (29.5 kg)
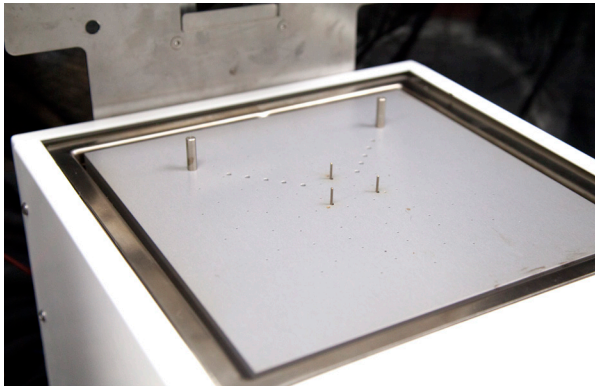- Shipping weight: 148 lb (67.1 kg)

## RELIABILITY

- Exceptional uptime
- 1-year full warranty on parts and labor
- Free remote technical support (phone, email, fax) for the life of the product
- Application process assistance for the life of the product

## EXHAUST BAKE HOOD DESIGN

- All-stainless-steel construction
- Exhausted hood for removal of process chemicals
- Optional nitrogen purge for inert bake environment

## UTILITIES

- Voltage ranges: 100, 110-125, 208-240 VAC
- Power requirements: 1683 watts (max) per plate
- Exhaust port: 1 inch OD
- Vacuum: 20 to 25 inches Hg
- Exhaust: 5 to 10 cfm
- $N_2$ (for bake plate proximity): 35 psi

## DATASTREAM™ TECHNOLOGY: CONNECTING THE SEMICONDUCTOR INDUSTRY

Cee® has released DataStream™ technology on its new Apogee™ tool line. DataStream™ technology gives you access to all of your connected Apogee™ manufacturing equipment in one place to track, access, and modify your systems via a website or mobile app. This technology will give manufacturers the ability to process and visualize data in real time and search and export that data into a number of different formats.

### Real-Time Process Information

- Constant feedback of process information for monitoring critical process parameters
- Streamlined interface between different tool types
- Visual cues on process status & health

### Advanced Recipe Creation

- Seamless switching between basic and advanced recipe creation methods
- Plain-English recipe translation
- Pre-defined process commands
- Unlimited process steps
- Unlimited recipe storage

### Environmental Monitoring

- Monitoring of temperature & humidity allows for stricter control of critical processes
- Set preconditions and tolerances for monitored parameters
- On-screen, colored visual cues for deviation from controlled specs

### Data Logging & Export

- Export data logs into commonly readable formats for further analysis and process troubleshooting
- Increase process efficiency
- Identify process control deviations
- Analyze multiple processes for best known method (BKM) development